

Notice of References Cited

Application/Control No.

09/938,435

Applicant(s)/Patent Under

Reexamination

WON ET AL.

Examiner

Christopher G. Paulraj

Art Unit

1773

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-6,451,390	09-2002	Goto et al.	427/579
	B	US-6,427,623	08-2002	Ko	118/723 E
	C	US-6,143,666	11-2000	Lin et al.	438/725
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	F	US-6,225,601	05-2001	Beer et al.	219/390
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	M	US-			

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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Ekbundit et al., Characterization of film uniformity in LPCVD TEOS Vertical Furnace, 2002 IEEE/SEMI Advanced Semiconductor Manufacturing Conference, pp 38-42
	V	Lee et al., The Effect of Patterned Susceptor on the Thickness Uniformity of Rapid Thermal Oxides, IEEE Transactions on Semiconductor Manufacturing, vol. 12, no. 3, pp 340-344
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)

Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.